

2012 International Symposium on EUV Lithography

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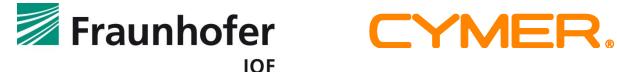
Brussels, October 2, 2012

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- Introduction
- Update on EUV coating infrastructure @ Fraunhofer IOF
- Optical performance and collector lifetime
- Summary and acknowledgement



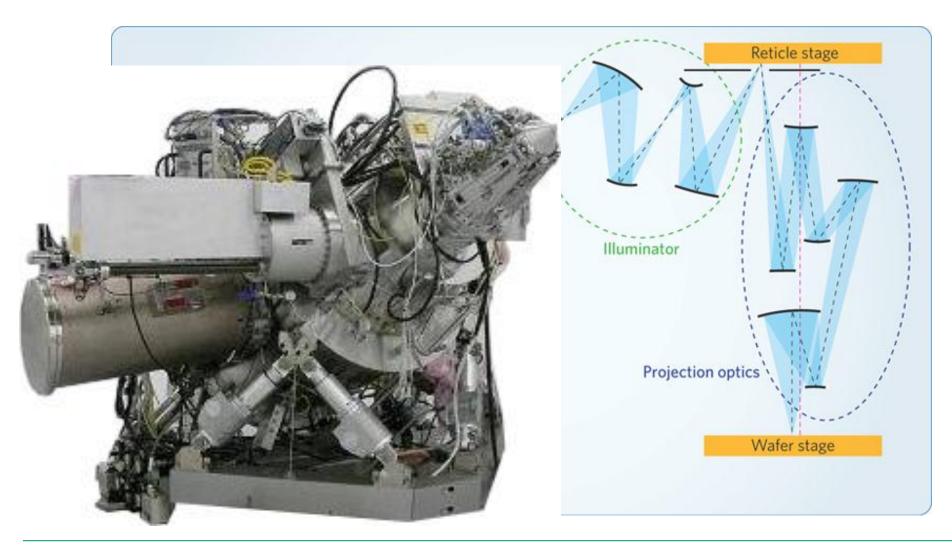


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Coating and characterization of LPP collector optics



[Nature Photonics 4, 24-26 (2010), www.cymer.com]





LPP collector coating challenges

R > 65 %

$$\lambda = (13.5 \pm 0.03) \text{ nm}$$

$$\rightarrow \Delta d = 0.015 \text{ nm} = 15 \text{ pm}$$

- Diameter: > 660 mm
- Lens sag: > 150 mm
- > 45 deg Tilt:
- Weight: > 40 kg







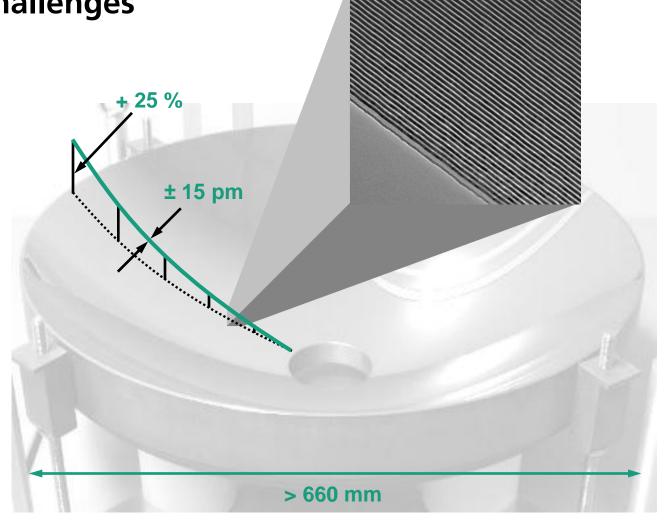
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NESSY I

- Substrate size: up to Ø 450 mm
- four deposition targets
- deposition of graded multilayers on curved substrates
- Installation: 2003
- Application: EUV optics







NESSY II

- Substrate size: up to Ø 700 mm
- six deposition targets
- deposition of graded multilayers on curved substrates
- Installation: 2009
- Application: collectors







NESSY III – delivery to IOF: September 25, 2012

- Substrate size: up to Ø 200 mm
- six deposition targets
- deposition of graded multilayers on curved substrates
- Installation: Sept. 2012
- Application: EUVL R&D







NESSY III – first EUV reflectance results

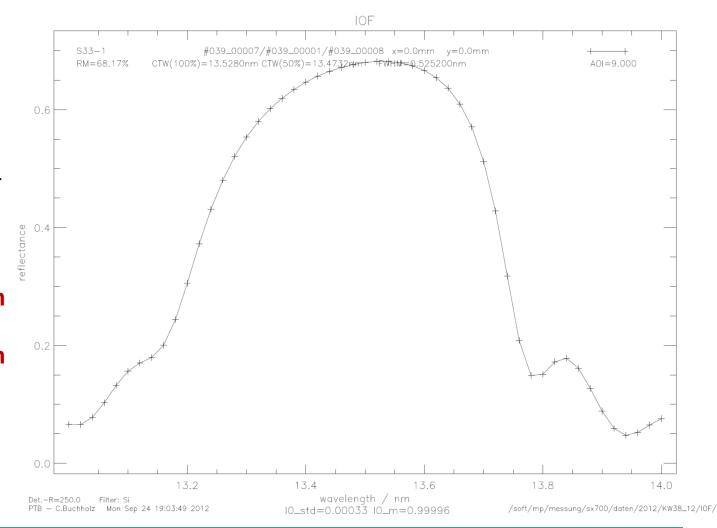
Very first Mo/Si multilayer

■ Reflectance: R = 68.2 %

Peak: λ = 13.53 nm

Center: $\lambda = 13.47 \text{ nm}$

FWHM: 0.525 nm





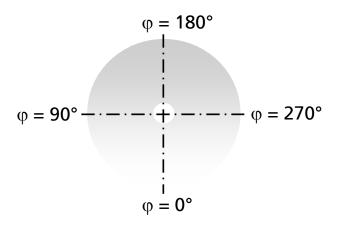


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Reflectivity (s-pol.) of LPP collector mirror



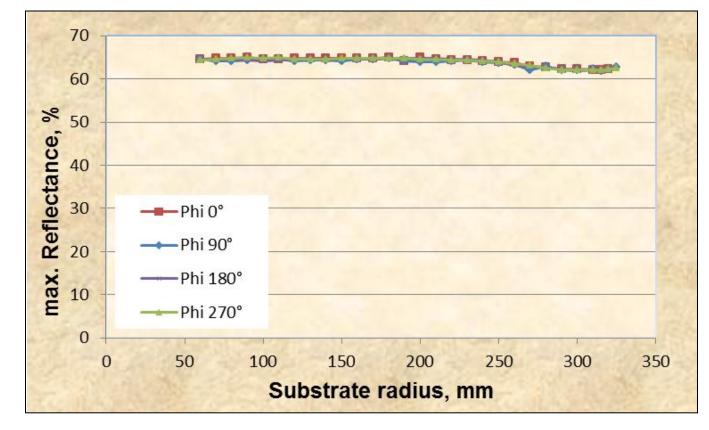
Maximum reflectance along four lines within clear aperture of collector mirror:

R = 65% ... 63 %

CHAMPION DATA:

R = 67 % ... 65 %

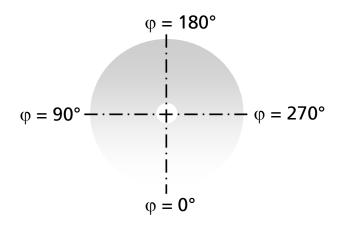
Measurements: PTB Berlin







Wavelength of LPP collector mirror



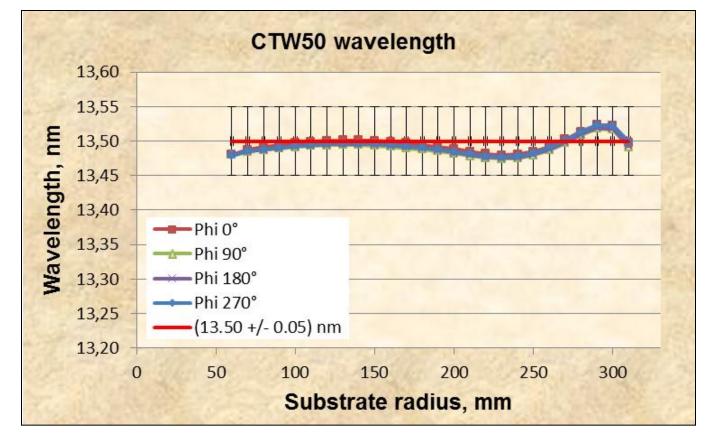
Center wavelength along four lines within clear aperture of collector mirror:

$$\lambda = (13.50 \pm 0.03) \text{ nm}$$

CHAMPION DATA:

 $\lambda = (13.500 \pm 0.015) \text{ nm}$

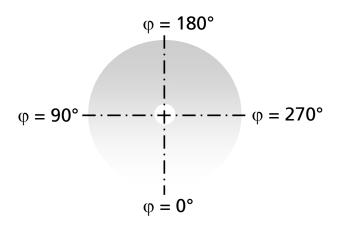
Measurements: PTB Berlin







Wavelength of LPP collector mirror



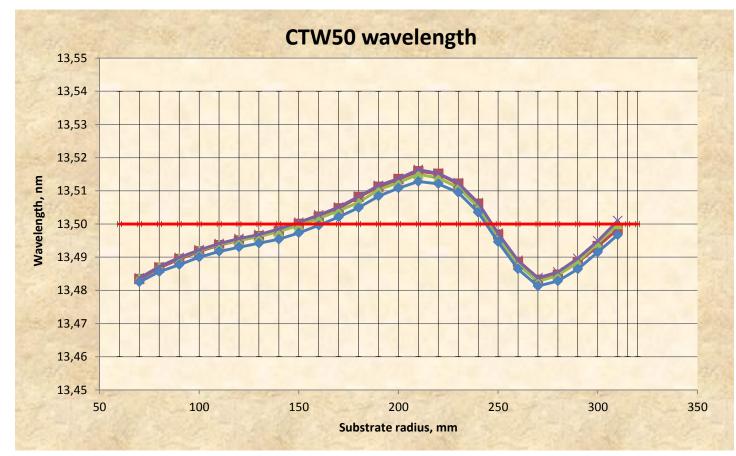
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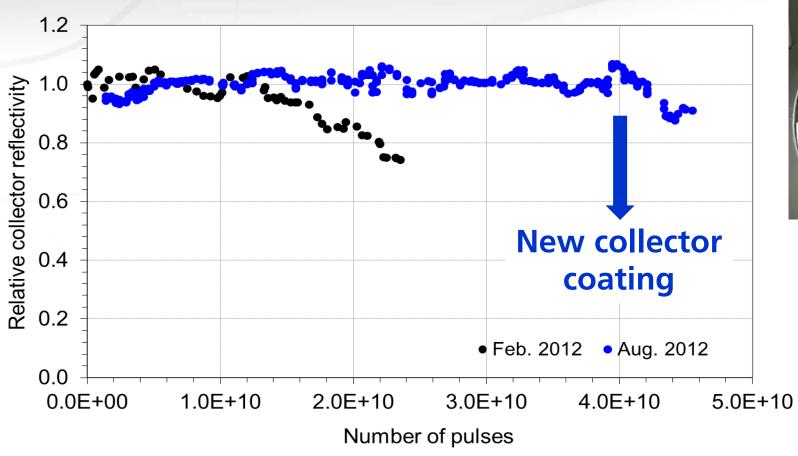
Measurements: PTB Berlin

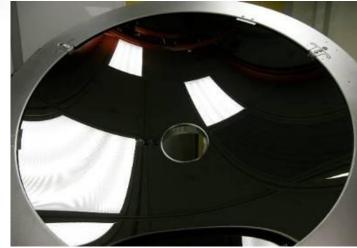


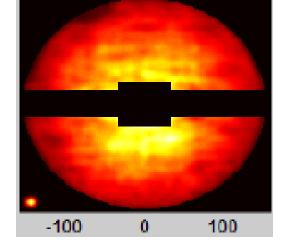




Improved Collector Lifetime in the Field >45 X 10⁹ Pulses at Original Reflectivity



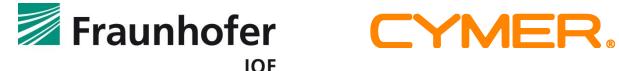




No change visible in far field image after 45 X 10⁹ pulses with a new coating

EUV Image at 45 Billion Pulses

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Summary

- Collector lifetime: 45 Billion pulses with new collector coating
- 2011 EUVL Symposium champion data now routinely achieved:
 - R = 65 % ... 63 % and d-spacing accuracy of Δd < 25...15 pm routinely achieved on LPP EUV multilayer mirror (Ø > 660 mm)
 - R = 67 % ... 65 % and d-spacing accuracy of Δd < 7 pm champion data achieved on LPP EUV multilayer mirror (Ø > 660 mm)
- Collector refurbishment: EUV reflectance 90 % recovered



Acknowledgements

- EUV source development team @ Cymer:
 - David Brandt, Igor Fomenkov, Silvia De Dea, and many others
- **EUV** reflectivity measurement team @ PTB Berlin:
 - Frank Scholze, Christian Laubis, Christian Buchholz, Annett Barboutis, Martin Biel, Benjamin Dubreau, Jana Puls, Christian Stadelhoff
- **EUV** collector team @ Fraunhofer IOF:
 - Christoph Damm, Andreas Gebhardt, Tobias Herffurth, Robert Jende, Johannes Paul Jobst, Thomas Müller, Viatcheslav Nesterenko, Michael Scheler, Thomas Peschel, Stefan Risse, Sebastian Scheiding, Steffen Schulze, Ronald Schmidt, Mark Schürmann, Uwe Zeitner, and many others





Thank you!